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"RESPONSE UNDER 37 CFR 1.116-EXPEDITED PROCEDURE EXAMINING GROUP 1745

## IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF

HIROSHI SHIHO, ET AL.

: EXAMINER: CHEN, KIN CHAN

SERIAL NO: 10/529,742

FILED: JANUARY 6, 2006

: GROUP ART UNIT: 1765

FOR: POLISHING PAD FOR
SEMICONDUCTOR WAFER AND
LAMINATED BODY FOR POLISHING OF
SEMICONDUCTOR WAFER EQUIPPED
WITH THE SAME AS WELL AS
METHOD FOR POLISHING OF
SEMICONDUCTOR WAFER

Yeunsideral promy

8/15/07

## REQUEST FOR RECONSIDERATION

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

Responsive to the Office Action of June 8, 2007, Applicants request reconsideration

in view of the following remarks.

Remarks begin on page 2 of this paper.

Kich